		SHEET 1 OF
ATTY. DOCKET NO.	APPLICATION NO.	
MICRON.009DV1	08/932,228	
APPLICANT		
Schuegraf, et al.		
FILING DATE	GROUP	

Unknown

	U.S. PATENT DOCUMENTS								
EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE (IF APPROPRIATE)			
Ye.	4502914	03/05/85	Trumpp et al.	438	424				
Yh.	5087586	02/11/92	Chan et al.	438	429				
<u>Jh</u>	5169491	12/08/92	Doan	438	693				
Vm	5191509	03/02/93	Wen	257	304				
Vh	5302233	04/12/94	Kim et al.	438	692				
Va	5366590	11/22/94	Kadomura	438	723				
<u>k</u>	5470783	11/28/95	Chiu et al.	438	446				
<u>\</u>	5530293	06/25/96	Cohen et al.	257	752				

September 17, 1997

U ST DEPARTMENT OF COMMERCE 5 1997 PATENT AND TRADEMARK OFFICE

SHEETS IF NECESSARY)

ORMATION DISCOSURE STATEMENT
BY ARE ICANT

FORM PTO 1449

EXAMINER INITIAL	OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)						
<u>√</u>	2 792	Kirk-Othmer, Encyclopedia of Chemical Technology, Second Completely Revised Edition, Vol. II, 1966. pp. 791-792.					
		Silicon Processing for the VLSI ERA, Isolation Technologies for Integrated Circuits, Vol. II, Ch. 2, pp. 12-83					

EXAMINER HUNG K. VU	DATE CONSIDERED 08/02/98	
*EXAMINER: INITIAL IF CITATION CONS. CONFORMANCE AND NOT CONSIDERED. INCLUD		9: DRAW LINE THROUGH CITATION IF NOT IN

HNY-1332:mc/jc2 120297